

Title (en)

PROCESS FOR FORMING A FLOW-RESISTANT RESIST MASK OF RADIOATION-SENSITIVE MATERIAL

Publication

EP 0000702 B1 19811007 (DE)

Application

EP 78100337 A 19780710

Priority

US 82246877 A 19770808

Abstract (en)

[origin: US4125650A] Resist images are hardened so that they are flow resistant at elevated temperatures by coating the image with a layer of a quinone-diazide hardening agent and heating the image to cause the agent to react with the resist and form a hardened image.

IPC 1-7

G03F 7/26

IPC 8 full level

G03F 7/00 (2006.01); **G03F 7/40** (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP US)

G03F 7/40 (2013.01 - EP US)

Cited by

US2018037973A1

Designated contracting state (EPC)

DE FR GB

DOCDB simple family (publication)

US 4125650 A 19781114; DE 2861132 D1 19811217; EP 0000702 A1 19790221; EP 0000702 B1 19811007; JP S5429574 A 19790305; JP S5649452 B2 19811121

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US 82246877 A 19770808; DE 2861132 T 19780710; EP 78100337 A 19780710; JP 8217678 A 19780707